# PLUS Search Results for S/N 10/643,718, Searched January 23, 2004 (Top 50)

5212397	5719081	5498554	5433168	4411060
5279978	5866468	5501994	5604150	4559638
5731619	5892256	5747850	5612230	4616242
5789286	6002158	6072217	5914245	4621276
6005285	6180985	5315144	5940324	4633030
6204153	6194253	5501993	5942781	4893164
4914491	6239469	5814866	5994162	5250835
5250460	6335542	6100567	6137142	5258322
4499558	6344116	5010385	6140161	5372958
5612246	4584027	5395773	6188136	5399514

### 10643718 CLS

## Most Frequently Occurring Classifications of Patents Returned From A Search of 10/643,718 on January 23, 2004

### **Combined Classifications**

- 9 257/E27.112
- 8 257/347
- 6 257/E27.064
- 5 257/E21.644
- 5 438/228
- 4 257/351
- 4 257/E21.544
- 4 438/527
- 3 257/349
- 3 257/350
- 3 257/369
- 3 257/371
- 3 257/372
- 3 257/66
- 3 257/E21.215
- 3 257/E21.435
- 3 257/E21.567
- 3 257/E27.06
- 3 257/E27.067
- 3 257/E29.061
- 3 257/E29.062
- 3 438/200
- 3 438/231
- 3 438/479
- 3 438/526
- 2 148/DIG 150
- 2 257/344
- 2 257/354
- 2 257/365
- 2 257/376
- 2 257/377
- 2 257/392
- 2 257/408
- 2 257/E21.106
- 2 257/E21.413
- 2 257/E21.415
- 2 257/E21.443
- 2 257/E21.564
- 2 257/E21.633
- 2 257/E21.703
- 2 257/E27.015
- 2 257/E29.055
- 2 257/E29.086
- 2 257/E29.107 2 257/E29.281
- 2 438/149
- 2 438/154
- 2 438/290
- 2 438/406
- 2 438/481

- 2 438/517
- 2 438/529 2 438/928

#### 10643718 CLSTITLES

Titles of Most Frequently Occurring Classifications of Patents Returned From A Search of 10/643,718 on January 23, 2004

8 257/347 (3 OR, 5 XR) Class 257: ACTIVE SOLID-STATE DEVICES 257/264 ... Enhancement mode or with high resistivity channel (e.g., doping of 10 15 cm -3 or less) 257/288 .Having insulated electrode (e.g., MOSFET, MOS diode) 257/347 ..Single crystal semiconductor layer on insulating substrate (SOI) 6 257/E27.064 (0 OR, 6 XR) Class 257: ACTIVE SOLID-STATE DEVICES 257/E27.006 .Including piezo-electric, electro-resistive, or magneto-resistive component (EPO) 257/E27.009 .Including semiconductor component with at least one potential barrier or surface barrier adapted for rectifying, oscillating, amplifying, or switching, or Including integrated passive circuit elements (EPO) 257/E27.01 ..With semiconductor substrate only (EPO) 257/E27.046 ...Including only semiconductor components of a single kind, e.g., all bipolar transistors, all diodes, or all CMOS (EPO) 257/E27.059 ....Including field-effect component only (EPO) 257/E27.06 .....Field-effect transistor with insulated gate (EPO) 257/E27.062 .....Complementary MIS (EPO) 257/E27.064 ......Combination of complementary transistors having a different structure, e.g. stacked CMOS, high-voltage and low-voltage CMOS (EPO) (1 OR, 4 XR) 5 438/228 Class 438: SEMICONDUCTOR DEVICE MANUFACTURING: PROCESS 438/142 MAKING FIELD EFFECT DEVICE HAVING PAIR OF ACTIVE REGIONS SEPARATED BY GATE STRUCTURE BY FORMATION OR ALTERATION OF SEMICONDUCTIVE ACTIVE REGIONS 438/197 .Having insulated gate (e.g., IGFET, MISFET, MOSFET, etc.) 438/199 .. Complementary insulated gate field effect transistors (i.e., CMOS) 438/218 ...Including isolation structure ....Recessed oxide formed by localized 438/225 oxidation (i.e., LOCOS) .....Having well structure of opposite 438/227 conductivity type 438/228 .....Plural wells 4 257/351 (2 OR, 2 XR) Class 257: ACTIVE SOLID-STATE DEVICES 257/264 ... Enhancement mode or with high resistivity

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channel (e.g., doping of 10 15 cm -3 or less)

257/288 .Having insulated electrode (e.g., MOSFET, MOS

diode)

257/347 ...Single crystal semiconductor layer on

insulating substrate (SOI)

257/350 ...Insulated electrode device is combined with

diverse type device (e.g., complementary MOSFETs, FET with

resistor, etc.)

257/351 ....Complementary field effect transistor

structures only (i.e., not including bipolar transistors,

resistors, or other components)

4 438/527 (1 OR, 3 XR)

Class 438: SEMICONDUCTOR DEVICE MANUFACTURING: PROCESS

438/510 INTRODUCTION OF CONDUCTIVITY MODIFYING DOPANT

INTO SEMICONDUCTIVE MATERIAL

438/514 .lon implantation of dopant into semiconductor

region

438/527 ...Including multiple implantation steps